

HELFGOTT & KARAS, P.C.  
Empire State Building  
60th Floor  
New York, NY 10118

Telephone: (212) 643-5000  
Facsimile: (212) 643-2166  
or 643-0420

**FACSIMILE TRANSMITTAL SHEET**

DATE : February 26, 2001  
TO : Examiner John S. Chu  
COMPANY : U.S. Patent and Trademark Office  
FAX NO. : 703-872-9367  
FROM : Michael I. Markowitz, Esq.

---

Total Number of Pages including cover 4

Re: U.S. Patent Application No.: 09/036,219  
**CHEMICALLY AMPLIFIED RESIST LARGE IN  
TRANSPARENCY AND SENSITIVITY TO EXPOSURE...**  
Our Reference No.:NEKW 14.868

---

This communication is confidential and intended to be privileged pursuant to the attorney-client privilege and the work product doctrine. If the reader of this message is not the intended recipient, you are hereby notified that any dissemination, distribution or copying of this communication is strictly prohibited. Anyone who receives this communication in error please immediately notify us by telephone. Thank you.

**DRAFT**

Filed Via Express Mail

Rec. No.:

On:

By:

LINDA E. HASTINGS

Any fee due as a result of this paper, not covered by an  
enclosed check, may be charged on Deposit Acct. No. 08-  
1634.

Attorney Docket No.: NEKW14.868**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN  
TRANSPARENCY AND SENSITIVITY TO EXPOSURE  
LIGHT LESS THAN 248 NANOMETER WAVELENGTH  
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

DATE

Assistant Commissioner for Patents  
Washington, D.C. 20231

**RESPONSE TO OFFICE ACTION**

S I R :

In response to the Office Action mailed on November 29, 2000, the period for  
responding thereto having been set to expire on February 28, 2001, please amend the  
above-captioned application as follows: